

Program schedule

Day 1 (June 25, 2019) Venue: Hall B (Conference Centre)		
Time	Event	Speaker/Instructor
8.00 – 8.45 am	Registration	
9.00-9.10 am	Lighting lamp and opening ceremony	
9.10-9.30 am	Inaugural speech	Director, IIT Mandi
9.30-10.30	Keynote lecture 'CMOS Manufacturing in India - Challenges and Issues'	Shri H. S. Jatana, SCL Mohali
10.30-11.00 am	High Tea	
11.00 am – 12.15 pm	Lithography: Art and science of IC manufacturing - Part I	Dr. Mahadeva Bhat GAETEC Hyderabad
12.15 pm -1.15pm	DUV Lithography and hardware – Part I	Er. Arpit Saraswat SCL Mohali
1.15-2.15 pm	Lunch Break	
2.30-5.30 pm	Demonstration (South campus)	
Day 2 (June 26, 2019) Venue: Hall B (Conference Centre)		
9.00-10.15 am	VLSI Design	Dr. Hitesh Srimali IIT Mandi
10.15 – 11.30 am	Lithography: Art and science of IC manufacturing - Part II	Dr. Mahadeva Bhat GAETEC Hyderabad
11.30 – 11.50 am	Tea	
11.50 am – 1.00 pm	DUV Lithography and hardware – Part II	Er. Arpit Saraswat SCL Mohali
1.00-2.00	Lunch Break	
2.30-5.00 pm	Demonstration (South campus)	
Day 3 (June 27, 2019) Venue: Hall B (Conference Centre)		
9.00-10.15 am	Molecular Beam Epitaxy and High electron mobility transistors	Dr. Mahadeva Bhat GAETEC Hyderabad
10.15 – 11.30 am	Recent Trends in IC Technology: From Materials to Devices – Part I	Dr. Satinder K. Sharma IIT Mandi
11.30 am – 11.50 am	Tea	
11.50 – 1.00 pm	Photolithography and soft lithography for Micro- and Nano-Fabrication – Part I	Dr. Chandra Shekhar Sharma IIT Hyderabad
1.00-2.00 pm	Lunch Break	
2.30-5.00 pm	Demonstration (South campus)	

Day 4 (June 28, 2019) Venue: Hall B (Conference Centre)		
9.00-10.00 am	Photolithography and soft lithography for Micro- and Nano-Fabrication – Part II	Dr. Chandra Shekhar Sharma IIT Hyderabad
10.00 – 11.30 am	Electron-Beam Lithography – Part –I	Dr. Prashant Verma SAC Ahmedabad
11.30 – 11.50 am	Tea	
11.50 am– 1.00 pm	Practical aspects of electron beam lithography -Part I	Dr. Ananth Venkatesan IISER Mohali
1.00-2.00 pm	Lunch Break	
2.30.-5.30	Demonstration (South campus)	
Day 5 (June 29, 2019) Venue: Hall B (Conference Centre)		
9.00-10.00 am	Keynote lecture Next Generation Lithography (NGL)	Prof. Kenneth E. Gonsalves IIT Mandi
10.00 – 11.30 am	Electron Beam Lithography – Part II	Dr. Prashant Verma SAC Ahmedabad
11.30 – 11.50 am	Tea	
11.50 am – 1.00 pm	Practical aspects of electron beam lithography – Part II	Dr. Ananth Venkatesan IISER Mohali
1.00-2.00 pm	Lunch Break	
2.30-5.30	Demonstration (South campus)	
Day 6 (June 30, 2019)		
9 am – 5.30 pm	Excursion	
Day 7 (July 1, 2019) Venue: Hall B (Conference Centre)		
9.00-10.00 am	Optical Lithography	Er. Siva Penmetsa CNSE, IISc Bangalore
10.00 – 11.00 am	MEMS device fabrication	Er. Yatish Prasad, STAR-C, Bangalore
11.00 – 11.15 am	Tea	
11.15 am – 12.15 pm	Wet etching	Dr. Vanita Agarwal, SSPL, Delhi
12.15-1.15 pm	High Resolution Imaging, Nanofabrication and Analysis	Er. Vignesh, ZEISS
1.15 -2.15 pm	Lunch Break	
2.30 – 5.30 pm	Demonstration (South campus)	
Day 8 (July 2, 2019) Venue: Hall B (Conference Centre)		
9.00-10.00 am	Bio-MEMS based micro-fluidic biosensing system	Prof. Raman C. Suri IIT Ropar
10.00 – 11.00 am	Wafer Cleaning	Er. Chiranjeevi Lakavath, STAR-C, Bangalore
11.00 – 11.15 am	Tea	
11.15 am – 12.15 pm	Dry etching	Er. Siva Penmetsa CNSE, IISc Bangalore

12.15 pm - 01.00 pm	Indigenization of electronic materials @ IIT Mandi – a team effort	Dr. Subrata Ghosh IIT Mandi
1.00 -1.15 pm	Vote of Thanks	Dr. Pradeep Parameswaran IIT Mandi
1.15 – 2.30 pm	Lunch Break	
End of the School		